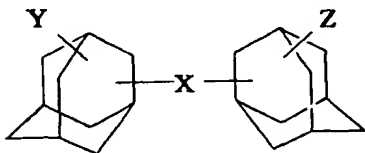


ABSTRACT

A resist composition comprises: at least one type of a first compound having two or more intramolecular adamantyl structures represented by the chemical formula 1 below; a base resin; and a second compound which generates an acid by active beam irradiation.

[Chemical formula 1]



wherein X is $-(\text{OCO})_m-(\text{CH}_2)_n-(\text{COO})_m-$, where $m = 0$ or 1 and $n = 0, 1, 2$ or 3 provided when $n = 0$, $m = 0$; and Y and Z are H, OH, F, Cl, Br, R or COOR, where Y may be Z, or Y and Z may be introduced in a single adamantyl structure and R represents a straight or branched alkyl group having 1 to 8 carbon atoms.

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